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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/734,635	12/12/2000	Hidetaka Oka	A-22141/US/A/CGJ 118	4752

324 7590 01/24/2002

CIBA SPECIALTY CHEMICALS CORPORATION
PATENT DEPARTMENT
540 WHITE PLAINS RD
P O BOX 2005
TARRYTOWN, NY 10591-9005

EXAMINER

CLARKE, YVETTE M

ART UNIT	PAPER NUMBER
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1752

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DATE MAILED: 01/24/2002

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary

Application No.

09/734,635

Applicant(s)

OKA ET AL.

Examiner

Yvette M Clarke

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-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 12 December 2000.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-18 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-18 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
- Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
- 11) ☐ The proposed drawing correction filed on _____ is: a) ☐ approved b) ☐ disapproved by the Examiner.
- If approved, corrected drawings are required in reply to this Office action.
- 12) ☐ The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. §§ 119 and 120

- 13) ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☒ All b) ☐ Some * c) ☐ None of:
1. ☒ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).
- * See the attached detailed Office action for a list of the certified copies not received.
- 14) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).
- a) ☐ The translation of the foreign language provisional application has been received.
- 15) ☐ Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

Attachment(s)

- 1) ☒ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☒ Information Disclosure Statement(s) (PTO-1449) Paper No(s) 2-3.
- 4) ☐ Interview Summary (PTO-413) Paper No(s) _____.
- 5) ☐ Notice of Informal Patent Application (PTO-152)
- 6) ☐ Other:

DETAILED ACTION

This is written in reference to application number 09/734635 filed on December 12, 2000.

Priority

1. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Information Disclosure Statement

2. The Information Disclosure Statements filed on May 24, 2001 and July 11, 2001 have been entered and fully considered.

Claim Rejections - 35 USC § 112

3. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter, which the applicant regards as his invention.

4. Claims 1-18 use improper Markush language to present the group from which component (A) and (B) are selected, respectively. Acceptable Markush language recites members as being "selected from the group consisting of A, B, and C."
5. Claims 1-18 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention. The claims as written are confusing in regard to the definition of Ar₁. The examiner has interpreted claim 1 to present one large Markush group wherein Ar₁ is a C₆-C₂₀ aryl or C₆-C₂₀ aryloyl, which can be unsubstituted or substituted with any of the listed compounds. The examiner recognizes that double

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inclusion within a Markush group is not prohibited however in this incidence it does render the claims unclear.

Claim Rejections - 35 USC § 102

6. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

7. Claims 1-10, 12-16 and 18 are rejected under 35 U.S.C. 102(b) as being anticipated by Laridon et al. (US 4282309A). Laridon teaches a photosensitive composition suited for the production of polymer resist images comprising a mixture of (1) a photopolymerizable ethylenically unsaturated compound, (2) at least one oxime ester photopolymerization initiator, and (3) at least one sensitizer (abstract). Specific oxime esters are represented by the formulae:



wherein R₄ represents a C₁₋₂ alkyl group, an aryl group, an alkaryl group, an aralkyl group, a hydroxy-substituted aralkyl group or a substituted or unsubstituted acyl group. R₅ is a hydrogen atom, a C₁₋₂ alkyl group, an aryl group, or a substituted or unsubstituted acyl group. R₆ represents a substituted or unsubstituted acyl group (c. 2, l. 44-68). It is the examiner's position that when R₅ is hydrogen, the limitations of claimed formula (I) are met. The photosensitive recording composition of the taught invention can be coated in the form of a layer on a support (c. 6, l. 3-5). It may comprise one or more ethylenically unsaturated polymerizable compounds such as

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styrene, acrylamide, acrylonitrile and methyl methacrylate (c. 6, l. 5-11). The photosensitive layer preferably comprises plurally unsaturated photopolymerizable compounds such as divinylbenzene, diglycol diacrylates, and pentaerythritol triacrylate (c. 6, l. 29-40). The said photopolymerizable compound can be used together with a polymeric binding agent. Suitable binding agents are polystyrene, polyvinyl acetate, copolymers of acrylic acid, methacrylic acid and unsaturated dicarboxylic acids such as maleic acid. Especially suitable are the alkali soluble copolymers of methyl methacrylate and methacrylic acid (c. 7, l. 1-46),

Laridon teaches many uses of the taught invention. If the support is made of a transparent resin or glass, photosensitive layers containing dyes or pigments can be used to make transparencies. If the support is made of an opaque paper, and the photosensitive layer contains dyes or pigments, opaque color proofs can be made by washing off. If the support is made of metal a photoresist can be prepared with a photosensitive coating according to the taught invention wherein the resist can be used as an etch resist (c. 8, l. 28-38). For the production of planographic printing plates, intaglio and relief images, and printed circuits, the substrates maybe stone, paper, and metal based materials suitable for etching (c. 8, l. 39-58). In the production of miniaturized integrated electrical components, the photosensitive composition serves as a shielding pattern on a semiconductor substrate wherein the desired electronic properties are added by techniques such as ion implantation, electrode-less deposition, ion milling or etching (c. 8, l. 59-66). The photosensitive recording material is prepared by coating the taught photosensitive layer on a selected substrate by known coating

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techniques. The coating composition may comprise besides the taught ingredients, matting agents, antistatic agents, coating aid. Examples include silica particles, which meet the limitation of inorganic filler as set forth in instant claim 10. Before their application in the form of a coating these ingredients are dissolved in a low boiling solvent, which is removed by evaporation after coating (c. 9, l. 45-60). The photosensitive coating is exposed to actinic radiation whereby the exposed areas are polymerized and the unexposed portions are removed by washing with a solvent (c. 10, l. 43-68). Any source of actinic radiation can be used in the range of 200-400 nm (c.11, l. 3-15). See also claims 1, 3 and 5-9.

Claim Rejections - 35 USC § 103

8. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

9. Claim 17 is rejected under 35 U.S.C. 103(a) as being unpatentable over Laridon et al. (US 4282309 A) as applied to claims 1-10, 12-16 and 18 above. Laridon teaches many uses of the taught invention. For example if the support is made of a transparent resin or glass, photosensitive layers containing dyes or pigments can be used to make transparencies. If the support is made of an opaque paper, and the photosensitive layer contains dyes or pigments, opaque color proofs can be made by washing off. In the production of miniaturized integrated electrical components, the taught photosensitive composition serves as a shielding pattern on a semiconductor substrate wherein the

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desired electronic properties are added by techniques such as ion implantation, electrode-less deposition, ion milling or etching (c. 8, l. 59-66). One of ordinary skill in the art would have been motivated by these teachings to coat the taught composition in combination with pigment or dye onto a transparent substrate comprising an electrode in order to obtain a desired electronic component (i.e., a color filter).

10. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.


- Laridon et al. (GB 2029423 A and EP 0014012 A1) which are in the same patent family as the cited prior art reference to Laridon (US 4282309 A).
- Laridon et al. (US 4255513 A) which teach a photopolymerizable recording material comprising an oxime ester.
- Birbaum et al. (US 6057380 A) which teach a photogeneration of amines from α -aminoacetophenones.

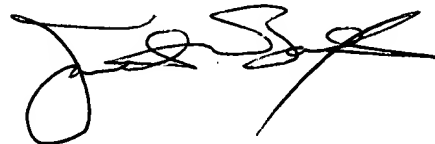
11. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Yvette M Clarke whose telephone number is 703-305-0589. The examiner can normally be reached on Monday-Thursday 7-5:30.

12. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Janet Baxter can be reached on 703-308-2303. The fax phone numbers for the organization where this application or proceeding is assigned are 703-872-9310 for regular communications and 703-872-9311 for After Final communications.

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13. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-1193.

ymc 
January 22, 2002



JANET BAXTER
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 1700